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## Conductance and gating effects at sputtered oxide interfaces

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# A

## **Self-consistent Schrödinger-Poisson calculation**

## A.1. Introduction

The self-consistent Schrödinger-Poisson (S-P) model was first used by F. Stern to study energy levels, populations, and charge distributions in  $n$ -type inversion layers on  $p$ -type Si in 1972 [133]. It has also been used by several groups to provide valuable insights into experimental results in  $\text{LaAlO}_3/\text{SrTiO}_3$  heterostructures [89, 90, 128, 132, 135].

In the S-P model, quantum effects are taken into account in the effective mass approximation, and the envelope wave function is assumed to vanish at the surface [133]. Compared to Si inversion layers, calculations for the  $\text{LaAlO}_3/\text{SrTiO}_3$  interface are more complicated, which is due to the anisotropic effective mass of the Ti  $3d$  orbitals and the field-dependent permittivity of the  $\text{SrTiO}_3$  substrate [62, 91].

### A.1.1. Anisotropic effective mass of Ti $3d$ orbitals

The  $\text{LaAlO}_3$  film is grown on a  $\text{SrTiO}_3$  (001) substrate, and the S-P calculation is performed along the growth direction, *i.e.* the  $z$  direction. The effective masses of the  $d_{xy}$  and  $d_{xz,yz}$  subbands are anisotropic. We take the masses of the various bands as

$$\begin{aligned} m_{xy}^{x,y} &= m_l, & m_{xy}^z &= m_h; \\ m_{xz}^{x,z} &= m_l, & m_{xz}^y &= m_h; \\ m_{yz}^{y,z} &= m_l, & m_{yz}^x &= m_h, \end{aligned} \quad (\text{A.1})$$

where  $m_l = 0.7m_e$  and  $m_h = 14m_e$  [89, 124, 134], with  $m_e$  being the mass of a free electron.

### A.1.2. Permittivity of $\text{SrTiO}_3$

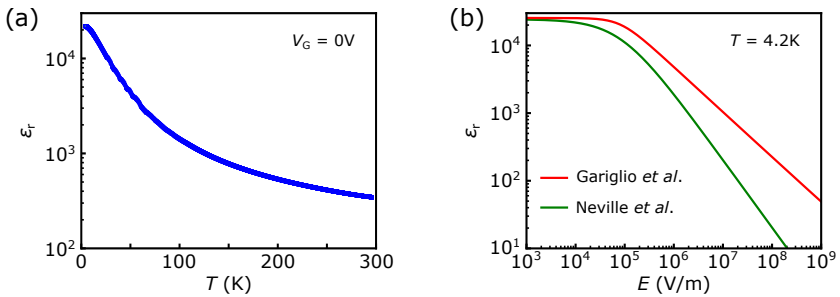


Figure A.1: (a) Temperature dependence of the permittivity ( $\epsilon_r$ ) of  $\text{SrTiO}_3$  without gate voltage applied. Image adapted from Ref. [62]. (b) Electric-field dependence of  $\epsilon_r$  at 4.2 K from two empirical expressions [123, 132].

$\text{SrTiO}_3$  single crystal has a temperature-dependent permittivity ( $\epsilon_r$ ) as shown in Fig. A.1(a), which reaches  $>20000$  at low temperature. However,  $\epsilon_r$  decreases when an electric

field ( $E$ ) is applied to the material. So far, the field dependence of  $\epsilon_r$  is still described by empirical expressions. Here, we discuss two widely used expressions. The first one was reported by Neville *et al.* [123]:

$$\epsilon_r(E) = \frac{1}{A(T) + B(T)|E|}, \quad (\text{A.2})$$

where  $A(T)$  is the inverse zero-field permittivity as a function of temperature, and  $B(T)$  is the field-dependent part as a function of temperature. At 4.2 K,  $A = 4.097 \times 10^{-5}$  and  $B = 4.907 \times 10^{-10}$  m/V for the (001) direction. The second one was reported by Gariglio *et al.* [132]:

$$\epsilon_r(E) = 1 + \frac{B}{[1 + (E/E_0)^2]^{1/3}}, \quad (\text{A.3})$$

where  $B = 25462$ , and  $E_0 = 82213$  V/m. It can be seen from Fig. A.1(b) that the two curves overlap well in low fields but differ a lot in high fields. In LaAlO<sub>3</sub>/SrTiO<sub>3</sub> heterostructures, the typical electric field at the interface is on the order of  $10^7$  V/m. Therefore, the two expressions can lead to very different results. We use Eq. (A.3) in our calculation.

## A.2. Self-consistent Schrödinger-Poisson calculation

The S-P model involves the Schrödinger equation

$$\left( -\frac{\hbar^2}{2m_\alpha^z} \frac{d^2}{dz^2} + eV(z) \right) \psi_{n\alpha}(z) = \epsilon_{n\alpha} \psi_{n\alpha}(z), \quad n = 1, 2, 3, \dots, \quad (\text{A.4})$$

and the Poisson equation

$$-\frac{d}{dz} \left( \epsilon_0 \epsilon_r(E(z)) \frac{d}{dz} V(z) \right) = \rho_{3D}(z), \quad (\text{A.5})$$

where  $\alpha = xy, xz, yz$  labels the Ti  $t_{2g}$  orbitals ( $d_{xy}, d_{xz}, d_{yz}$ ),  $V(z)$  is the confining potential,  $\psi_{n\alpha}(z)$  and  $\epsilon_{n\alpha}$  are normalized wave function and eigen value of the  $n$ th sub-band of the  $\alpha$  orbital, respectively,  $\epsilon_0$  is the vacuum permittivity, and  $\rho_{3D}(z)$  is the three-dimensional (3D) charge distribution.

At the LaAlO<sub>3</sub>/SrTiO<sub>3</sub> interface, electrostatic confinement is described by the confining potential  $V(z)$ , which can be calculated by the Poisson equation. For a given charge distribution and electrostatic boundary conditions,  $V(z)$  is uniquely defined. On the other hand, for a given  $V(z)$ , the distribution of mobile electrons is determined by the population of bound states in  $V(z)$ , which can be calculated by the Schrödinger equation. Therefore, the coupling between these two equations could enable a self-consistent calculation of  $V(z)$ . A schematic of the self-consistent S-P calculation is shown in Fig. A.2.

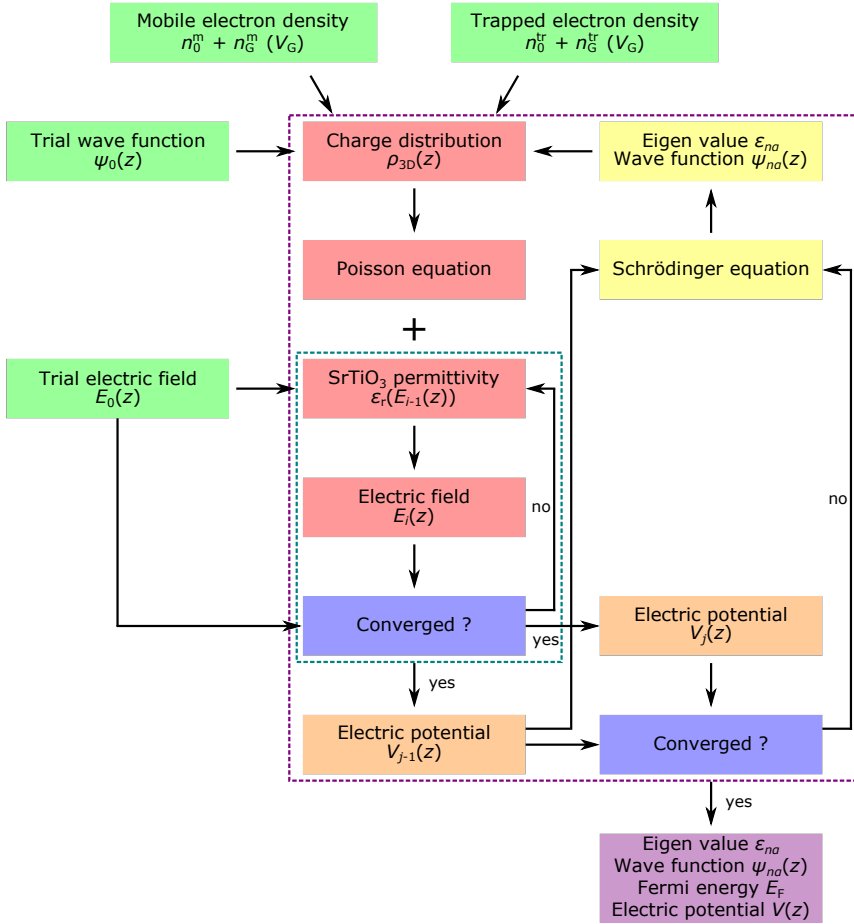


Figure A.2: Schematic of the Schrödinger-Poisson calculation, which contains two self-consistent loops. The first loop (dotted teal box) is for calculating the electric field  $E(z)$  and the second loop (dotted purple box) for the electric potential  $V(z)$ .

### A.2.1. Input parameters

Input parameters of the S-P calculation include the initial mobile electron density  $n_0^m$ , the initial trapped electron density  $n_0^{\text{tr}}$ , the gate-induced mobile electron density  $n_G^m(V_G)$ , the gate-induced trapped electron density  $n_G^{\text{tr}}(V_G)$ , a trial wave function  $\psi_0(z)$ , and a trial electric field  $E_0(z)$ . Now we discuss them one by one.

#### Initial mobile and trapped electron density

Initial mobile electron density  $n_0^m$  is the sheet carrier density of the virgin state, which is obtained from magnetotransport measurement. In our sample,  $n_0^m = 1.41 \times 10^{13} \text{ cm}^{-2}$ . Initial trapped electron density  $n_0^{\text{tr}}$  can only be obtained from trial and error until the calculated results cover the experimental results. In our case,  $n_0^{\text{tr}} = 6.4 \times 10^{13} \text{ cm}^{-2}$ . We take  $z \geq 0$  to be SrTiO<sub>3</sub> and  $z < 0$  to be LaAlO<sub>3</sub>. The positive charge density is  $n_0^m + n_0^{\text{tr}}$  on the LaAlO<sub>3</sub> side as the boundary condition, which keeps an overall charge neutrality.

#### Gate-induced mobile and trapped electron density

In back-gating experiment, the total amount of electrons  $n_G^{\text{tot}}(V_G)$  induced by the gate voltage ( $V_G$ ) can be calculated using a parallel plate capacitor model [130, 131]:

$$n_G^{\text{tot}}(V_G) = \int_{V_1}^{V_2} \frac{\epsilon_0}{ed_{\text{STO}}} \epsilon_r(V_G) dV_G, \quad (\text{A.6})$$

where  $d_{\text{STO}} = 0.5 \text{ mm}$  is the thickness of the SrTiO<sub>3</sub> substrate, and  $E = V_G/d_{\text{STO}}$ . It should be noted that the electric field  $E$  here is considered to be position independent. The reason is that  $E$  only changes significantly at the interface within about 20 nm and is constant in the SrTiO<sub>3</sub> bulk. As discussed in Chapter 4, the gate-induced trapped electron density  $n_G^{\text{tr}}(V_G)$  can only be obtained from experimental results. In our sample,

$$n_G^{\text{tr}}(V_G) = N(1 - e^{-\frac{V_G}{400}}), \quad (\text{A.7})$$

where  $N = 6.2 \times 10^{13} \text{ cm}^{-2}$ . Therefore, the gate-induced mobile electron density

$$n_G^m(V_G) = n_G^{\text{tot}}(V_G) - n_G^{\text{tr}}(V_G). \quad (\text{A.8})$$

#### Trial wave function and trial electric field

A trial wave function ( $\psi_0(z)$ ) gives a first guess of the mobile charge distribution. We use the Fang-Howard variational wave function, which gives a good approximation for the ground state in the  $z$  direction [131]

$$\psi_0(z) = \sqrt{\frac{b^3}{2}} z e^{-\frac{bz}{2}}, \quad (\text{A.9})$$

where  $b$  is the variational parameter

$$b = \left( \frac{33\pi}{2} (n_0^m + n_G^m(V_G)) a_B^2 \right)^{\frac{1}{3}} \frac{1}{a_B}, \quad (\text{A.10})$$

where  $a_B$  is the Bohr radius

$$a_B = \frac{4\pi\epsilon_r\epsilon_0\hbar^2}{m^*e^2}. \quad (\text{A.11})$$

It should be noted that the actual input values for Eq. (A.11) do not affect the final results. We take  $\epsilon_r = 1$  and  $m^* = m_e$ .

A trial electric field ( $E_0(z)$ ) can be any reasonable value and we take  $E_0(z) = 1000 \text{ V/m}$ .

### A.2.2. Self-consistent calculation

First, we calculate the 3D charge distribution  $\rho_{3D}(z)$ , which is the sum of the distribution of mobile and trapped electrons,

$$\rho_{3D}(z) = \rho_{3D}^m(z) + \rho_{3D}^{\text{tr}}(z). \quad (\text{A.12})$$

The mobile charge distribution is given by

$$\rho_{3D}^m(z) = -e(n_0^m + n_G^m(V_G)) |\psi_0(z)|^2. \quad (\text{A.13})$$

The trapped charge distribution should also be obtained from trial and error. In our sample,

$$\rho_{3D}^{\text{tr}}(z) = \begin{cases} 0 & \text{for } z < 0 \\ -e \frac{n_0^{\text{tr}} + n_G^{\text{tr}}(V_G)}{\lambda} e^{-\frac{z}{\lambda}} & \text{for } z \geq 0 \end{cases} \quad (\text{A.14})$$

where  $\lambda = 50 \text{ nm}$ .

Integration of Eq. (A.5) along the  $z$  direction gives

$$-\epsilon_0\epsilon_r(E(z)) \frac{d}{dz} V(z) = -\epsilon_0\epsilon_r(E(z)) E(z) = \int_0^L \rho_{3D}(z) dz, \quad (\text{A.15})$$

where the integration range is from 0 to  $L = 100 \text{ nm}$ , which is divided into 2000 equal sections.

Now we enter the first self-consistent loop for calculating  $E(z)$  as shown in Fig. A.2. The convergence is checked by

$$\eta = \frac{1}{L} \int_0^L \left( \frac{E_i(z) - E_{i-1}(z)}{E_i(z)} \right)^2 dz. \quad (\text{A.16})$$

If  $\eta$  is large than the error tolerance  $\epsilon_p$  (set to  $10^{-5}$ ), a new electric field ( $E'_i(z)$ ) is calculated by the over relaxation method in order to get a faster convergence

$$E'_i(z) = \zeta E_{i-1}(z) + (1 - \zeta) E_i(z), \quad (\text{A.17})$$



where  $\zeta = 0.3$ . If  $\eta$  is smaller than  $\epsilon_p$ , the calculation is converged. Integration of  $E_i(z)$  along the  $z$  direction gives the electric potential  $V_{j-1}(z)$ .

Next,  $V_{j-1}(z)$  is injected into Eq. (A.4). The outcome of solving the Schrödinger equation is the eigen values ( $\epsilon_{n\alpha}$ ) and the normalized wave functions ( $\psi_{n\alpha}(z)$ ) of the subbands of different  $t_{2g}$  orbitals. We can calculate the mobile charge distribution again with  $\epsilon_{n\alpha}$  and  $\psi_{n\alpha}(z)$ :

$$\rho_{3D}^m(z) = -e \sum_{n,\alpha} \Theta(E_F - \epsilon_{n\alpha}) \frac{\sqrt{m_\alpha^x m_\alpha^y}}{\pi \hbar^2} (E_F - \epsilon_{n\alpha}) |\psi_{n\alpha}(z)|^2, \quad (\text{A.18})$$

where  $\Theta$  is the Heaviside step function and  $E_F$  is the Fermi energy.  $E_F$  can be obtained by numerically solving

$$n_0^m + n_G^m(V_G) = \sum_{n,\alpha} \Theta(E_F - \epsilon_{n\alpha}) \frac{\sqrt{m_\alpha^x m_\alpha^y}}{\pi \hbar^2} (E_F - \epsilon_{n\alpha}). \quad (\text{A.19})$$

A new  $\rho_{3D}(z)$  is obtained by summing up Eq. (A.14) and Eq. (A.18).

Now we enter the larger self-consistent loop for calculating  $V(z)$  as shown in Fig. A.2. By treating the new electric potential  $V_j(z)$  and  $V_{j-1}(z)$  with the same manner as shown in Eq. (A.16) and Eq. (A.17), a converged electric potential  $V(z)$  can be obtained.

The subband dispersion can be calculated by

$$E_{n\alpha} = \frac{\hbar^2 k_x^2}{2m_\alpha^x} + \frac{\hbar^2 k_y^2}{2m_\alpha^y} + \epsilon_{n\alpha}, \quad (\text{A.20})$$

where  $k_x$  and  $k_y$  are the wavevector in the  $x$  and  $y$  directions, respectively.

